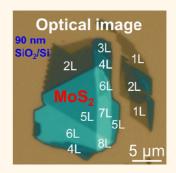
Rapid and Reliable Thickness Identification of Two-Dimensional Nanosheets Using Optical Microscopy

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ABSTRACT The physical and electronic properties of ultrathin two-dimensional (2D) layered nanomaterials are highly related to their thickness. Therefore, the rapid and accurate identification of single- and few- to multilayer nanosheets is essential to their fundamental study and practical applications. Here, a universal optical method has been developed for simple, rapid, and reliable identification of single- to quindecuple-layer (1L—15L) 2D nanosheets, including graphene, MoS₂, WSe₂, and TaS₂, on Si substrates coated with 90 or 300 nm SiO₂. The optical contrast differences between the substrates and 2D nanosheets with different layer numbers were collected and tabulated, serving as a standard reference, from which the layer number of a given nanosheet can be readily and reliably determined without using complex calculation or expensive instrument. Our general optical identification method will facilitate the thickness-dependent study of various 2D nanomaterials and expedite their research toward practical applications.



KEYWORDS: thickness identification · optical microscopy · 2D nanosheets · graphene · MoS₂ · WSe₂ · contrast difference

wo-dimensional (2D) layered nanomaterials, such as graphene and transition metal dichalcogenides (TMDs, e.g., MoS₂, WSe₂, and TaS₂), 1-10 have attracted much attention in recent years due to their novel optical, electronic, mechanical, and magnetic properties in contrast to their bulk crystals. Currently, mechanical exfoliation is still one of the most efficient ways to obtain high-quality, atomically thin nanosheets of 2D layered nanomaterials. 1,3-7 However, this technique produces not only single- and few- to multilayer nanosheets but also a large quantity of thicker flakes. It is well-known that the physical and electronic properties of 2D nanomaterials are highly related to their thickness. 3-6,11-17 Therefore, the rapid determination of location and layer number of mechanically exfoliated single- and few- to multilayer nanosheets among copious thick flakes over a centimeter/millimeter-size area is the first priority in their fundamental research and practical applications.

To date, many methods have been developed to identify the thickness of 2D nanosheets, such as atomic force microscopy

(AFM), Raman spectroscopy, and optical microscopy (OM). Although AFM is commonly used to measure the thickness of 2D nanosheets, it is time-consuming and not suitable for rapid measurement over large area. In addition, AFM measurement might be affected by the absorbed water layer under 2D nanosheets or instrumental offset. 18,19 As a result, the thickness of single-layer graphene measured by AFM varied from 0.4 to 0.9 nm. 19-21 Raman spectroscopy is a quick characterization method to identify single- to few-layer 2D nanosheets. 12,17,22-24 However, the difference between double- and few-layer graphene or TMD nanosheets in Raman spectra is insufficient to accurately distinguish them. 4,22,23 Although low-frequency Raman spectroscopy (<50 cm⁻¹) has been used to reliably determine the layer number of graphene, MoS₂, or WSe₂, 12,17,24 it requires expensive and nonstandard equipment. On the contrary, OM is a simple, efficient, and nondestructive technique that enables rapid characterization of 2D nanosheets over a large area. 4,13,18,25-34 The OM method mainly relies on the optical contrast

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between a 2D nanosheet and the substrate for fast and unambiguous identification. To improve such contrast, several methods have been developed, including the use of narrow band illumination, ^{27,35} selection of optimal substrate, ^{25,29,35} collection of reflection spectra, ¹⁸ measurement of total color difference, ²⁹ or ratio of color difference ²⁸ etc. Unfortunately, these methods involve either special experimental setup or timeconsuming image processing, and more importantly, they are not generalizable for identification of various kinds of nanosheets.

Here, we demonstrate a simple, rapid, and reliable method to identify 2D nanosheets (e.g., graphene, MoS₂, WSe₂, and TaS₂) from single- to quindecuple-layer (1L–15L) without using any instrument or complex calculation. The contrast difference between the 2D nanosheet and substrate can be simply obtained from the brightness profile of their color images or grayscale images of the R, G, or B channel. The obtained values of contrast difference for nanosheets with different layer numbers can be plotted as a standard chart, based on which the layer number of a given nanosheet can be rapidly and accurately determined on the Si substrate coated with 90 or 300 nm SiO₂, referred to as 90 or 300 nm SiO₂/Si, respectively.

RESULTS AND DISCUSSION

Description of the Optical Identification Method. The key to the reliable and accurate optical identification of a 2D nanosheet is to correlate its layer number with its optical contrast with respect to the substrate. In our method, the optical contrast of a nanosheet (defined as C) and substrate (defined as C_S) was directly measured from its color optical image by using a free software (ImageJ). The contrast difference (defined as C_D) is obtained by subtracting C with C_S (eq 1). Similarly, for the grayscale image (from the R, G, or B channel), the contrast difference between the nanosheet and substrate (C_{DR} , C_{DG} , or C_{DB}) is calculated by subtracting the contrast of the nanosheet (C_{R} , C_{G} , or C_B) with that of the substrate (C_{SR} , C_{SG} , or C_{SB}) (eqs 2—4).

$$C_{\mathsf{D}} = C - C_{\mathsf{S}} \tag{1}$$

$$C_{\rm DR} = C_{\rm R} - C_{\rm SR} \tag{2}$$

$$C_{DG} = C_{G} - C_{SG} \tag{3}$$

$$C_{\rm DB} = C_{\rm B} - C_{\rm SB} \tag{4}$$

As a demonstration, Figure 1a shows the color optical image of a MoS_2 flake on 90 nm SiO_2/Si . Figure 1b is the contrast profile of the dashed rectangle highlighted in Figure 1a generated by ImageJ. The contrast values (C) of the octuple-layer (8L) and hextuple-layer (6L) MoS_2 nanosheets are 162.3 and 118.6, respectively, while the contrast value of 90 nm SiO_2/Si (C₅) is 120.4. According to eq 1, the contrast difference

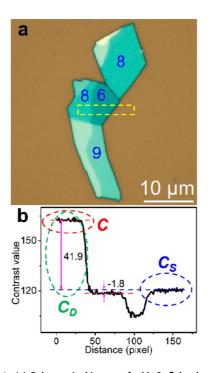


Figure 1. (a) Color optical image of a MoS_2 flake deposited on 90 nm SiO_2/Si . The digitals shown in (a) indicate the layer numbers of MoS_2 nanosheets, which were confirmed by AFM (Figure S1 in Supporting Information). (b) Contrast profile of the dashed rectangle shown in (a). C_S : contrast of 90 nm SiO_2/Si . C: contrast of MoS_2 nanosheet. C_D : the contrast difference between MoS_2 nanosheet and 90 nm SiO_2/Si .

between the 8L (or 6L) MoS_2 nanosheet and 90 nm SiO_2/Si substrate is calculated to be $C_D = 162.3 - 120.4 = 41.9$ (or 118.6 - 120.4 = -1.8).

Optical Identification of 1L-15L Graphene Nanosheets on 90 and 300 nm SiO₂/Si. It has been reported that the color of a graphene nanosheet can be used to identify its thickness in combination with theoretical calculation.^{29,33} Theoretical calculation predicted that SiO₂ film with thickness of 90 or 300 nm is the optimal dielectric layer for optical identification of graphene. 13,25,34 Here, thickness identification of 1L-15L graphene nanosheets on 90 or 300 nm SiO₂/Si can be achieved by our simple, rapid, and reliable method based on the measurement of optical contrast difference. Color optical images (Figure 2a-n), AFM measurement (Figure 2g), and Raman characterization (Figure S2 in Supporting Information (SI)) were first used to locate exfoliated graphene nanosheets on 90 nm SiO₂/Si and determine their thicknesses. After that, optical contrast differences (C_D) between 1L-15L graphene nanosheets and 90 nm SiO₂/Si were measured from their color optical images taken at different exposure times by using ImageJ (Figure 2o). It can be seen that, for 1L-15L graphene nanosheets, the absolute value of C_D increases with increasing exposure time from 20 to 140 ms and decreases from 160 to 300 ms. At 200 ms, as compared to other exposure times, such as 80 ms, the CD values are mostly distinguishable among the 1L-15L nanosheets (Figure 2p

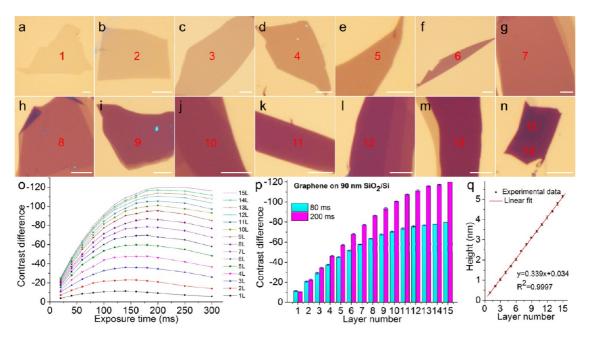


Figure 2. (a-n) Color optical images of 1L-15L graphene nanosheets on 90 nm SiO_2/Si . The scale bars shown in (a-n) are $10 \mu m$. The digitals shown in (a-n) indicate the layer numbers of corresponding graphene nanosheets. (o) Plot of measured C_D values of 1L-15L graphene nanosheets on 90 nm SiO_2/Si at the exposure times of 20, 40, 60, 80, 100, 120, 140, 160, 180, 200, 250, and 300 ms. (p) Plot of measured C_D values of 1L-15L graphene nanosheets on 90 nm SiO_2/Si at the exposure times of 80 and 200 ms. (q) Thickness of 1L-15L graphene nanosheets measured by AFM.

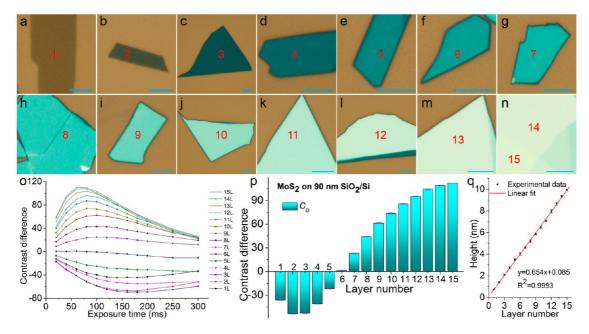


Figure 3. (a-n) Color optical images of 1L-15L MoS₂ nanosheets on 90 nm SiO₂/Si. The scale bar is 5 μ m for each image. The digitals shown in (a-n) indicate the layer numbers of corresponding MoS₂ nanosheets. (o) Plot of measured C_D values of 1L-15L MoS₂ nanosheets on 90 nm SiO₂/Si at exposure times of 20, 40, 60, 80, 100, 120, 140, 160, 180, 200, 250, and 300 ms. (p) Plot of C_D values of 1L-15L MoS₂ on 90 nm SiO₂/Si at exposure time of 80 ms. (q) Thickness of 1L-15L MoS₂ nanosheets measured by AFM.

and Table S1 in SI), especially for those thicker than 10L. Therefore, a standard chart of C_D values at 200 ms for different layer numbers was generated (Figure 2p and Table S1 in SI), from which the thickness of a graphene nanosheet on 90 nm SiO $_2$ /Si can be readily determined.

Similar to the C_D values, the C_{DR} , C_{DG} , and C_{DB} values of 1L-15L graphene nanosheets on 90 nm SiO_2/Si ,

measured from grayscale images of R, G, and B channels, respectively, can also be used for the layer number identification (Figure S3 and Table S1 in SI). Similarly, the C_D , C_{DR} , and C_{DG} values of 1L-13L graphene nanosheets on 300 nm SiO_2/Si can also be determined in the same manner and thus used for layer number identification of graphene (Figures S4 and S5 in SI).

Optical Identification of 1L-15L MoS₂ Nanosheets on 90 and **300 nm SiO₂/Si.** As for the 1L-15L MoS₂ nanosheets on 90 nm SiO₂/Si (Figure 3a-n), they also show the thickness-dependent contrast difference at various exposure times (Figure 3o,p), confirmed by AFM measurement and low-frequency Raman characterization (Figure 3q and Figure S6 in SI). It is shown that at the exposure time of 80 ms, 5L-15L MoS₂ nanosheets are distinguishable based on C_D values (Figure 3o,p and Table S2 in SI). However, the C_D values of 1L-4L MoS₂ nanosheets are less differentiable, and especially the $C_{\rm D}$ values of 2L and 3L nanosheets are close, ~ -55 (Figure 3p and Figure 4a,b). In order to effectively distinguish 1L-4L MoS₂ nanosheets on 90 nm SiO₂/Si, the optical contrast differences measured from their grayscale images from R, G, and B channels (C_{DR} , C_{DG} , and C_{DB}) were used to determine their thicknesses (Figure 4c-i). As shown in Figure 4g-i, the C_{DB} values of 1L and 2L MoS₂ nanosheets are negative (1L, -26.4; 2L, -15.4), while those of 3L and 4L MoS_2 nanosheets are positive (3L, 4.2; 4L, 28.5). Meanwhile, the C_{DR} and C_{DG} values of 1L−4L MoS₂ nanosheets are also discrete enough for their thickness identification (Figure 4d,f,i). Therefore, 1L-15L MoS₂ nanosheets on 90 nm SiO₂/Si can be easily identified based on the measured C_D , C_{DR} , C_{DG} , and C_{DB} values.

An interesting feature was observed in the plot of C_D (or C_{DR} , C_{DG} , and C_{DB}) versus layer number of MoS₂. For example, there is a transition of C_D value between 5L and 6L nanosheets (Figure 3p and Table S2 in SI) from negative C_D at 5L (-21.8 ± 0.5) to positive C_D at 6L (1.0 \pm 0.7). In other words, compared to the 90 nm SiO₂/Si substrate, 1L-5L MoS₂ nanosheets are darker while 6L-15L MoS₂ nanosheets are brighter under white light illumination. In this work, the thickness of a nanosheet with a minimum positive C_D value (similar for C_{DR} , C_{DG} , or C_{DB}) is defined as the transitional thickness (T_C) . In this case, the T_C for MoS₂ nanosheets in color image and grayscale images of the R, G, and B channels is 6L, 10L, 5L, and 3L, respectively (Table 1). Therefore, the sign (positive or negative) of the C_D value enables the fast determination of the thickness range of a nanosheet (i.e., below T_C or above T_C).

Similar to MoS_2 nanosheets on 90 nm SiO_2/Si , 1L-15L MoS_2 nanosheets on 300 nm SiO_2/Si can also be reliably identified by measuring the C_D value in combination with the C_{DR} , C_{DG} , and C_{DB} values (Figure 5a-o). The C_D values can be used to rapidly and reliably identify septuple-layer (7L) to 15L MoS_2 nanosheets but are less distinguishable among 1L-6L nanosheets (Figure 5n). In contrast to MoS_2 nanosheets on 90 nm SiO_2/Si (Figure 3), the transition of C_D occurs between 7L and 8L MoS_2 nanosheets on 300 nm SiO_2/Si , where 7L MoS_2 gives a negative C_D (-4.4 ± 0.2) and 8L MoS_2 gives a positive C_D (4.7 ± 0.3). The transition of C_D can be used as a mark to quickly determine a MoS_2 nanosheet thicker or thinner than 8L on 300 nm

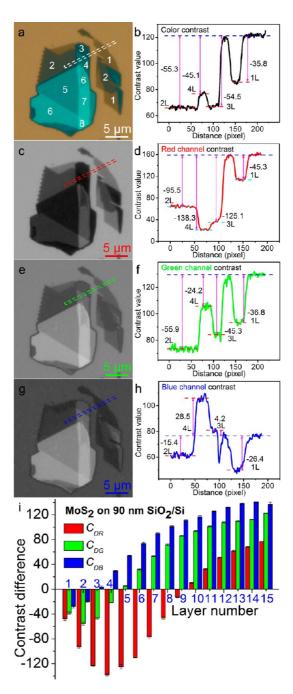


Figure 4. Color optical (a) and grayscale images of the (c) R, (e) G, and (g) B channels of MoS_2 flake on 90 nm SiO_2/Si . The digitals shown in (a) indicate the layer numbers of corresponding MoS_2 nanosheets. The corresponding contrast profiles of color optical (b) and grayscale images of the (d) R, (f) G, and (h) B channels of MoS_2 flake are obtained from the dashed rectangles shown in (a), (c), (e), and (g), respectively. (i) Plot of C_{DR} , C_{DG} , and C_{DB} values of $1L-15L\ MoS_2$ nanosheets on 90 nm SiO_2/Si .

SiO₂/Si. Meanwhile, the $C_{\rm DR}$, $C_{\rm DG}$, and $C_{\rm DB}$ values are used to identify 1L-6L MoS₂ nanosheets, which are difficult to be distinguished by the measurement of $C_{\rm D}$. For example, 1L-3L MoS₂ nanosheets can be differentiated by reading the $C_{\rm DR}$ values (Figure 5o and Table S2), whereas 4L-6L MoS₂ can be distinguished based on $C_{\rm DG}$ values (Figure 5o and Table S2).

TABLE 1. Transition Thickness of 2D Nanosheets with Minimum Positive Optical Contrast Difference on 90 and 300 nm SiO₂/Si

	90 nm SiO ₂ /Si				300 nm SiO ₂ /Si			
	$c_{\scriptscriptstyle D}$	$C_{ m DR}$	\mathcal{C}_{DG}	$\mathcal{C}_{ extsf{DB}}$	ζ_{D}	C_{DR}	C _{DG}	C _{DB}
graphene	$43L < T_C < 52L^a$	54L < T _C ^a	$43L < T_C < 52L^a$	$30L < T_C < 37L^a$	$46L < T_C < 51L^a$		\sim 46 L^a	
MoS_2	6L	10L	5L	3L	8L	16L	4L	1L
WSe ₂	7L	9L	7L	4L	8L	14L	5L	1L
TaS ₂	27L	22L	25L	3L				

^a See Figures S7 and S8 in SI for the detailed information.

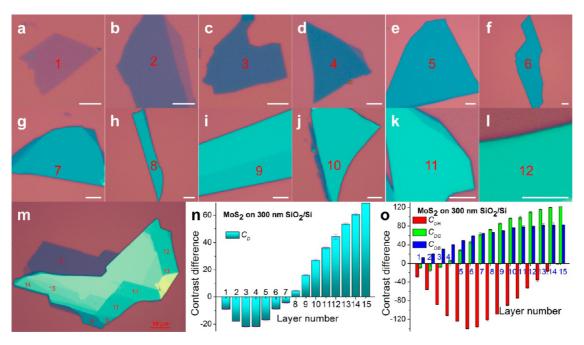


Figure 5. (a—m) Color optical images of $1L-15L \, MoS_2$ on $300 \, nm \, SiO_2/Si$. The scale bars are $5 \, \mu m$ for images a—l and $10 \, \mu m$ for image m. The digitals shown in (a—m) indicate the layer numbers of the corresponding MoS_2 nanosheets. Plots of (n) C_D values and (o) C_{DR} , C_{DG} , and C_{DB} values of $1L-15L \, MoS_2$ nanosheets on $300 \, nm \, SiO_2/Si$.

The $T_{\rm C}$ of $C_{\rm DG}$ is a 4L MoS $_2$ nanosheet (6.0 \pm 1.3); that is, the $C_{\rm DG}$ values of 1L-3L MoS $_2$ nanosheets are negative while those of 4L-6L MoS $_2$ nanosheets are positive (see Table S2 in SI for detailed information). The highest absolute value of $C_{\rm DR}$ was found at the 6L MoS $_2$ nanosheet. After that, the absolute $C_{\rm DR}$ values of 7L-15L MoS $_2$ nanosheets decrease linearly with the thickness. Therefore, 1L-15L MoS $_2$ nanosheets on 300 nm SiO $_2$ /Si can be readily identified using the $C_{\rm D}$ values in combination with the $C_{\rm DR}$ and $C_{\rm DG}$ values.

Optical Identification of Single- To Quattuordecuple-layer (1L-14L) WSe₂ Nanosheets on 90 and 300 nm SiO₂/Si. The optical contrast difference can also be used to identify 1L-14L WSe₂ nanosheets on 90 or 300 nm SiO₂/Si. Figure 6a-I shows the color optical images of 1L-14L WSe₂ nanosheets on 90 nm SiO₂/Si taken at the exposure time of 80 ms. The thickness of these nanosheets was confirmed by AFM measurement and low-frequency Raman spectra (Figure 6o and Figure S9 in SI). As shown in Figure 6m, the C_D values are distinguishable for 6L-14L WSe₂ nanosheets but are difficult

to be differentiated for 1L-5L nanosheets. As shown in Figure 6m and Table S3 in SI, the 2L-4L WSe₂ nanosheets have similar C_D values (2L, -59.2 ± 1.4 ; 3L, -62.9 ± 1.5 ; 4L, -55.3 ± 1.4), so do 1L and 5L WSe₂ nanosheets (1L, -38.4 ± 1.7 ; 5L, -36.8 ± 2.4). In this case, the grayscale images of R, G and B channels were used to indicate the difference among the 1L-5L WSe₂ nanosheets (Figure 6n). By comparing C_{DR} , C_{DG} , and C_{DB} values at various layer numbers, it was found that the C_{DR} values combined with CDB values are mostly suitable to rapidly differentiate 1L-5L WSe₂ nanosheets because of the sufficient gap between the C_{DR} and C_{DB} values of adjacent layer numbers (Table S3 in SI). The CDB value of 1L WSe₂ nanosheet is negative (-27.6 ± 1.4), while that of 5L WSe $_2$ nanosheet is positive (16.7 \pm 0.9). In addition, the $T_{\rm C}$ of $C_{\rm DB}$ values is the 4L WSe₂ nanosheet (0.3 \pm 0.8). Thus 1L, 4L, and 5L WSe₂ nanosheets can be easily identified by reading the C_{DB} values. Although 2L and 3L WSe₂ nanosheets have similar C_{DG} values $(2L, -76.8 \pm 1.4; 3L, -76.5 \pm 1.9)$, their C_{DR} values (2L, -80.0 ± 0.9 ; 3L, -103.0 ± 0.4) are fairly discrete for

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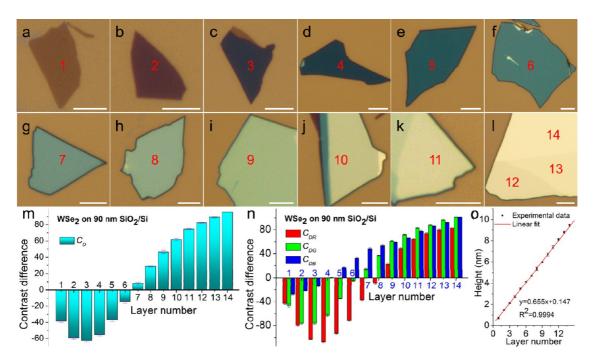


Figure 6. (a–I) Color optical images of 1L-14L WSe $_2$ nanosheets on 90 nm SiO $_2$ /Si. The scale bars shown in (a–I) are $5 \mu m$. The digitals shown in (a–I) indicate the layer numbers of corresponding WSe $_2$ nanosheets. Plots of (m) C_D and (n) C_{DR} , C_{DG} , and C_{DR} values of 1L-14L WSe $_2$ nanosheets on 90 nm SiO $_2$ /Si at the exposure time of 80 ms. (o) Thickness of 1L-14L WSe $_2$ nanosheets measured by AFM.

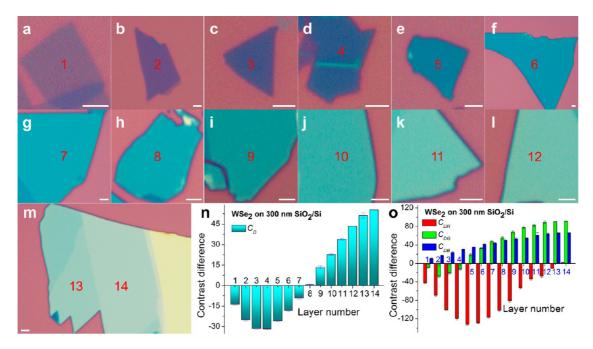


Figure 7. (a—m) Color optical images of 1L-14L WSe₂ on 300 nm SiO₂/Si. The scale bars shown in (a—m) are 2 μ m. The digitals shown in (a—m) indicate the layer numbers of the corresponding WSe₂ nanosheets. Plots of (n) C_D values and (o) C_{DR} , C_{DG} , and C_{DB} values of 1L-14L WSe₂ nanosheets on 300 nm SiO₂/Si.

thickness identification. Thus, 1L-14L WSe $_2$ nanosheets on 90 nm SiO $_2$ /Si can be readily identified using the C_D values in combination with C_{DR} and C_{DB} values. Furthermore, for 1L-14L WSe $_2$ nanosheets on 300 nm SiO $_2$ /Si, their C_D , C_{DR} , C_{DG} , and C_{DB} values are also distinguishable for fast thickness determination (Figure 7 and Table S3 in SI). In this case, the T_C of C_D is 8L (Table 1 and Table S3 in

SI) and the $C_{\rm D}$ values of 8L-14L WSe $_{\rm 2}$ can be used to rapidly and reliably distinguish them (Figure 7n). As for 1L-7L WSe $_{\rm 2}$ nanosheets, the $C_{\rm DR}$, $C_{\rm DG}$, and $C_{\rm DB}$ values are used to determine their thicknesses (Table S3 in SI and Figure 7o). Therefore, 1L-14L WSe $_{\rm 2}$ nanosheets on 300 nm SiO $_{\rm 2}$ /Si can be readily identified using the $C_{\rm D}$ values in combination with the $C_{\rm DR}$ and $C_{\rm DG}$ values.

Verification of Layer Number Identification of Graphene, MoS_2 , and WSe_2 Nanosheets on 90 nm SiO_2/Si . In order to verify the accuracy of our optical method, the thicknesses of mechanically exfoliated graphene, MoS_2 , and WSe_2 nanosheets on 90 nm SiO_2/Si were first identified using the measurement of C_D values followed by AFM measurement to confirm it.

With graphene as an example, Figure 8a shows the color optical image of a graphene nanosheet. As shown in Figure 8b, the C_D values measured from the red dashed rectangle shown in Figure 8a are -10.7, -57.6, and -68.3. According to the standard chart shown in Figure 2o,p and Table S1 in SI, these C_D values correspond to 1L, 5L, and 6L graphene nanosheets, respectively. AFM measurement on these regions show thicknesses of 0.4, 1.7, and 2.1 nm (Figure 8c,d), respectively, consistent with the thickness of 1L, 5L, and 6L graphene (Figure 2q and Table S4 in SI),

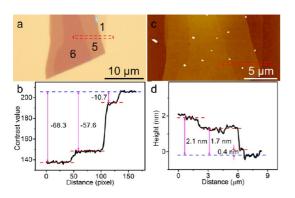


Figure 8. Color optical (a) and AFM height (c) images of graphene flake on 90 nm SiO₂/Si. The corresponding contrast difference (b) and height (d) profiles are obtained from the dashed rectangles shown in (a) and (c), respectively. The digitals shown in (a) indicate the layer numbers of corresponding graphene nanosheets.

confirming the accuracy of the optical identification result

As for MoS_2 , Figure 9a shows the color optical image of an exfoliated MoS_2 nanosheet, displaying three distinct color regions. C_D values measured from the red dashed rectangle shown in Figure 9a are -2.5, 22.4, and 60.3, which correspond, respectively, to 6L, 7L, and 9L MoS_2 nanosheets according to the standard chart shown in Figure 3o,p and Table S2 in Sl. The corresponding thicknesses of the these three regions measured by AFM (Figure 9c,d) are 4.1, 4.7, and 5.9 nm, respectively, consistent with those of 6L, 7L, and 9L MoS_2 nanosheets.

Similarly, for the optical identification of WSe₂ nanosheet, C_D values of 9.5 and 30.8 (Figure 9f) were first obtained from two different color regions (highlighted in the red dashed rectangle shown in Figure 9e), corresponding to 7L and 8L WSe₂ nanosheets, respectively, by referring to the standard chart shown in Figure 6m and Table S3 in Sl. AFM measurement (Figure 9g,h) on these two regions indicates thicknesses of 4.7 and 5.4 nm, respectively, in agreement with those of 7L and 8L WSe₂ nanosheets (Figure 6o and Table S4 in SI).

Besides graphene, MoS_2 and WSe_2 nanosheets, our method can also be used for the rapid and reliable identification of TaS_2 nanosheets on 90 nm SiO_2/Si . The C_D values of 2L-8L and 15L to octoviguple-layer (28L) and duotriguple-layer (32L) TaS_2 nanosheets are discrete enough for reliable identification (Table S5 and Figure S10 in SI). In combination with the C_{DR} , C_{DG} , and C_{DB} values (Table S5 in SI), 2L-28L and 32L TaS_2 nanosheets can be easily and reliably identified (Figures S10 and S11 in SI), indicating the generalizability of our method in the thickness identification of 2D nanosheets.

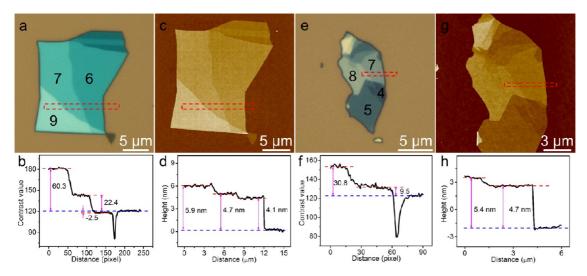


Figure 9. Color optical images of MoS_2 (a) and WSe_2 (e) nanosheets on 90 nm SiO_2/Si and the corresponding contrast profiles (b,f) obtained from the dashed rectangles in (a) and (e), respectively. AFM height images of MoS_2 (c) and WSe_2 (g) nanosheets on 90 nm SiO_2/Si , and the corresponding height profiles (d,h) obtained from the dashed rectangles in (c) and (g), respectively. The digitals shown in (a) and (e) indicate the layer numbers of corresponding MoS_2 and WSe_2 nanosheets, respectively.

The measurement of C_D is affected by the intensity of illumination, thickness of SiO₂ film, and exposure time. In this work, the exposure time is fixed. Therefore, the measurement error may arise from the thickness variation of commercial SiO2 film and fluctuation of illumination intensity, which is manually adjusted in our optical microscope (Figure S12 in SI). Take 6L MoS₂ as an example; the C_D value of 6L MoS₂ is 1.0 \pm 0.7 (Figure 3p and Table S2 in SI) when the 90 nm SiO₂/Si substrate (12 mm \times 12 mm) cut from the same wafer was used. However, the CD values of 6L MoS2 nanosheets shown in Figure 1a and Figure 9a are -1.8 and −2.5, respectively, when the 90 nm SiO₂/Si substrate (12 mm \times 12 mm) cut from another wafer was used. Nevertheless, we found that the C_D value variation of MoS₂ nanosheets on different wafers is usually smaller than 3, which is much smaller than the difference of C_D values between the adjacent layers. In other words, the difference among CD values is sufficient for thickness determination. In addition, the transition thickness (T_c) of optical contrast difference is related to the type of material, the thickness of SiO₂ film, as well as the color of optical image. As shown in Table 1, the T_{C} values of C_{D} , C_{DR} , C_{DG} , and C_{DB} follow the order of $C_{\rm DR} > C_{\rm D} \ge C_{\rm DG} > C_{\rm DB}$ for 1L-15L MoS₂ and 1L-14L WSe₂ nanosheets on 90 and 300 nm SiO₂/Si. In the case of TaS_2 nanosheets on 90 nm SiO_2/Si , the T_C values of C_D , C_{DR} , and C_{DG} follow the order of $C_D > C_{DG} > C_{DR}$ (Table 1). In terms of graphene nanosheets on 90 and

300 nm SiO₂/Si, the $T_{\rm C}$ values of $C_{\rm D}$, $C_{\rm DR}$, $C_{\rm DG}$, and $C_{\rm DB}$ are much larger compared to those of MoS₂, WSe₂, and TaS₂ nanosheets (Table 1 and Figures S7 and S8). The variation of $T_{\rm C}$ for different materials might be attributed to their intrinsic properties, such as refractive index.

CONCLUSION

In summary, a universal optical method has been developed for simple, rapid, and reliable identification of 1L-15L 2D nanosheets, including graphene, MoS₂, WSe₂, and TaS₂, on 90 and 300 nm SiO₂/Si. By processing the color optical images and the grayscale images of R, G, and B channels, the optical contrast differences between 2D nanosheets and SiO₂/Si were measured using ImageJ and plotted as standard charts to guide the layer number identification. The transition of C_{D_r} C_{DR} , C_{DG} , and C_{DB} values can be used as a clear mark for quick identification of layer number. Neither complex calculation nor special instrument is required in our method, making it applicable for any laboratories equipped with a standard optical microscope and digital camera. Our simple optical identification method will facilitate the fundamental study and practical applications of 2D nanomaterials and accelerate their progress toward future commercialization. Furthermore, our method potentially expands the capability of optical microscopy in the study of nanomaterials and applications of nanotechnology.

METHODS AND MATERIALS

Mechanical Exfoliation of 2D Nanosheets (Graphene, MoS₂, WSe₂, and TaS₂ Nanosheets). Natural graphite (NGS Naturgraphit GmbH, Germany), MoS₂ crystals (SPI Supplies, USA), WSe₂, and TaS₂ crystals (Nanoscience Instruments, Inc., USA) were used for preparation of mechanically exfoliated 2D nanosheets, which then were deposited onto the freshly cleaned 90 and 300 nm SiO₂-coated Si substrates (90 and 300 nm SiO₂/Si).

Capture of Optical Images of 2D Nanosheets. The bright-field optical microscope (Eclipse LV100D with a $100\times$, 0.9 numerical aperture (NA) objective, Nikon) was used to locate and image the 2D nanosheets. A lamphouse (LV-LH50PC) equipped with high-intensity halogen lamp (12 V, 50 W) was used as the light source. The intensity of the light source was adjusted by turning the brightness control knob to level 9 (Figure S12 in SI). For graphene and MoS₂ nanosheets on 90 nm SiO₂/Si, the optical images were captured at the exposure times of 20, 40, 60, 80, 100, 120, 140, 160, 180, 200, 250, and 300 ms. For WSe₂ and TaS₂ nanosheets on 90 nm SiO₂/Si, the optical images were captured at the exposure time of 80 ms. For various 2D nanosheets on 300 nm SiO₂/Si, the optical images were captured at the exposure time of 50 ms. A DS camera head (DS-Fi1) with a digital camera control unit (DS-U3) was used to capture color optical images of 2D nanosheets at the resolution of 1280 \times 960 pixels. The imaging software is NIS-Elements F (version 4.00.06), and the white balance is calibrated as R/B = 1.23:1.24 (Figure S12 in SI). In order to give quantitative and statistic characterization of the layer numbers of 2D nanosheets, a large amount of graphene, MoS₂, WSe₂, and TaS₂ flakes with layer numbers ranged from 1L to 32L, prepared by the mechanical cleavage technique, was imaged by optical microscopy and analyzed by using our optical method. For 1L to 10L 2D nanosheets, at least

five samples were collected for measurement. For 2D nanosheets thicker than 11L, usually three samples were collected for measurement.

Optical Contrast Difference Measurement of Color Optical Images and Grayscale Images of R, G, and B Channels by Using ImageJ. The color optical images of 2D nanosheets were processed by the ImageJ (version 1.46p, National Institutes of Health, USA). For the color image (RGB image), the contrast value of each pixel (C_V), that is, brightness value, is calculated using the following equation

$$C_{V} = (C_{VR} + C_{VG} + C_{VB})/3$$
 (5

where C_{VR} , C_{VG} , and C_{VB} are the R, G, and B values per pixel in color image, respectively; 0 is darkest, and 255 is brightest.

The grayscale images of R, G, and B channels were extracted by using the "Split Channels" command from "Image > Color > Split Channels" in the menu bar, where 0 is darkest and 255 is brightest. In the color or grayscale image, we can drag the left button of the mouse to draw a rectangular box across the 2D nanosheet and then press "K" to obtain the contrast profile of the selected area. In the plot of contrast profile, click "List" to show the contrast values of the 2D nanosheet and SiO_2 substrate.

The detailed optical contrast difference (C_D , C_{DR} , C_{DG} , and C_{DB}) values of 2D nanosheets are listed in Tables S1–S4 in SI.

Thickness Measurement of 2D Nanosheets by AFM. AFM (Dimension ICON with NanoScope V controller, Bruker, USA) was used to confirm the layer number of 2D nanosheets by measuring the film thickness in tapping mode in air. The thickness values of 2D nanosheets are listed in Table S4 in SI.

Raman Measurement of 2D Nanosheets. Analysis of the MoS_2 and WSe_2 nanosheets by low-frequency Raman spectroscopy was carried out at room temperature using a micro-Raman spectrometer (Horiba-JY T64000) equipped with a liquid-nitrogen-cooled

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charge-coupled device. The measurements were conducted in a backscattering configuration excited with a solid-state green laser ($\lambda=532$ nm). A reflecting Bragg grating (OptiGrate) followed by another ruled reflecting grating was used to filter the laser side bands, as such \sim 8 cm $^{-1}$ limit of detection was achieved using most solid-state or gas laser lines. All spectra were collected through a $100\times$ objective and dispersed by a 1800 g/mm grating under a triple subtractive mode with a spectra resolution of 1 cm $^{-1}$. The Raman spectra were calibrated by using the peak of Si substrate (520 cm $^{-1}$). The laser power at the sample surface was less than 1.5 mW for MoS $_2$ and 0.3 mW for WSe $_2$.

Analysis of graphene nanosheets by Raman spectroscopy was carried out on a WITec CRM200 confocal Raman microscopy system with the excitation line of 488 nm and an air cooling charge-coupled device (CCD) as the detector (WITec Instruments Corp., Germany).

Conflict of Interest: The authors declare no competing financial interest.

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